

Accepted Manuscript

Full Length Article

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PII: S0169-4332(18)30956-5
DOI: <https://doi.org/10.1016/j.apsusc.2018.04.006>
Reference: APSUSC 39005

To appear in: *Applied Surface Science*

Received Date: 8 December 2017
Revised Date: 28 March 2018
Accepted Date: 2 April 2018

Please cite this article as: S.Z. Szilasi, L. Juhasz, Selective etching of PDMS: Etching as a negative tone resist, *Applied Surface Science* (2018), doi: <https://doi.org/10.1016/j.apsusc.2018.04.006>

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Selective etching of PDMS: etching as a negative tone resist

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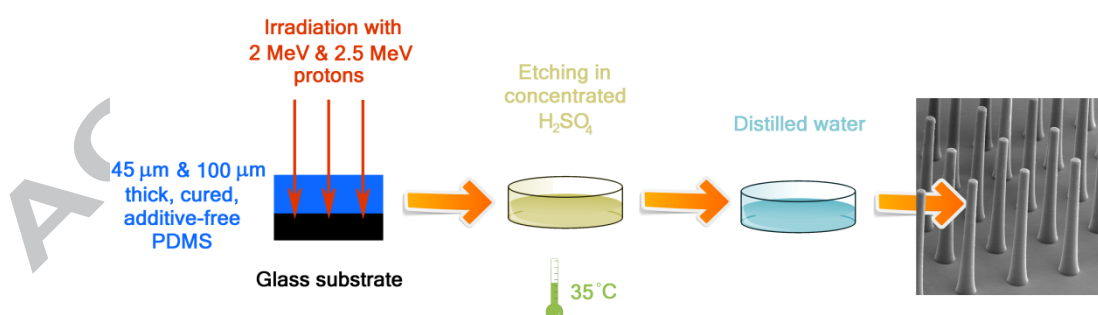
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